

FIG.1

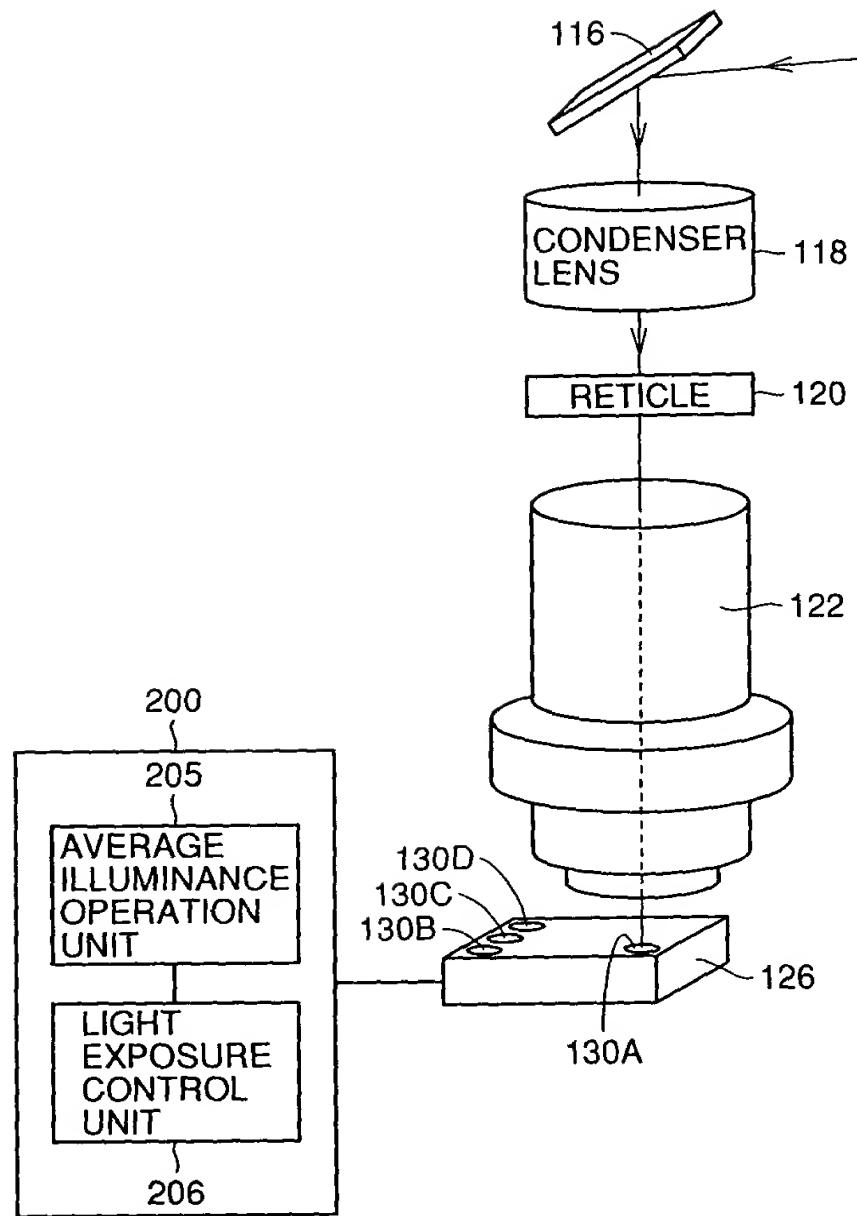


FIG.2

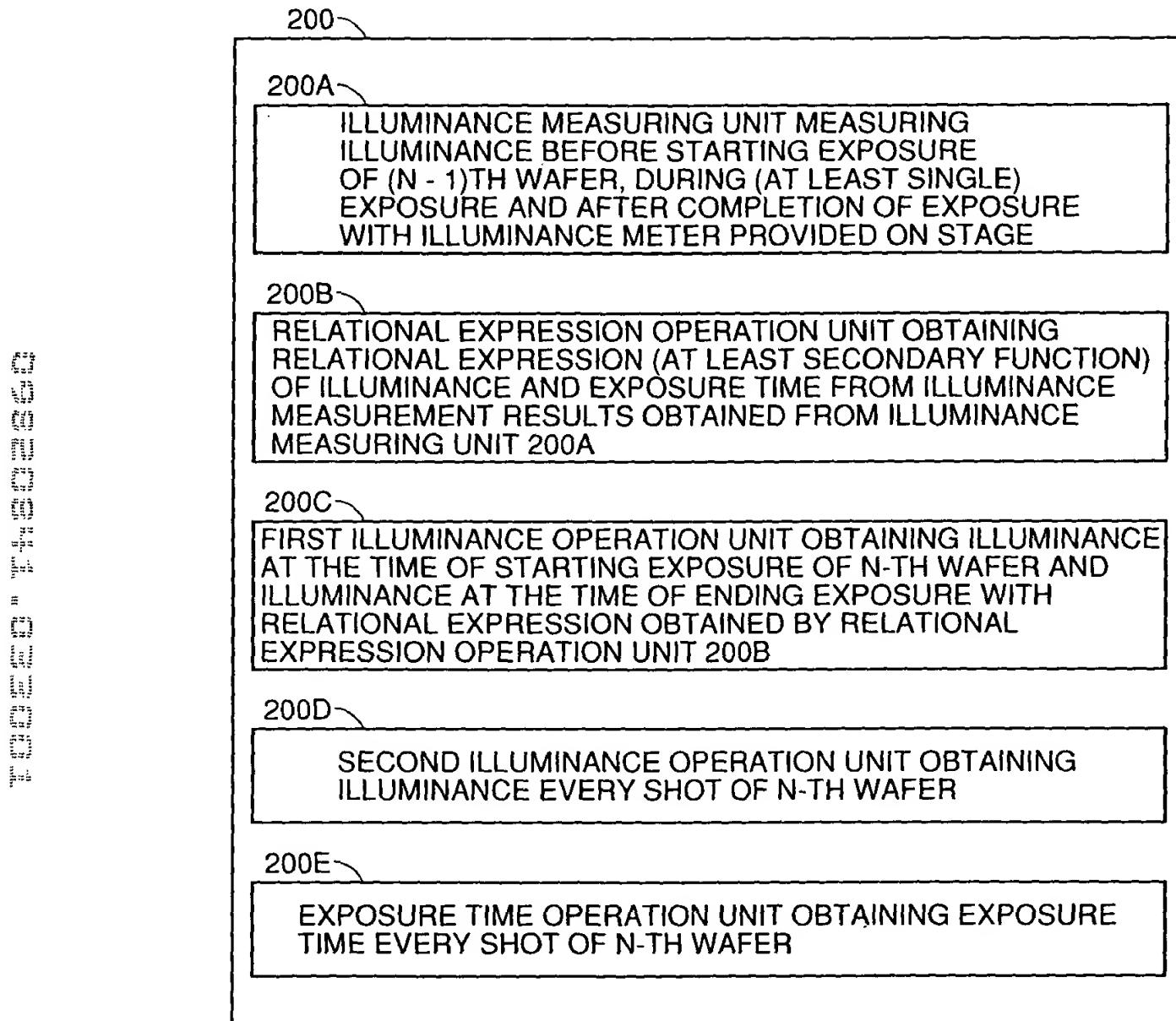


FIG.3

ILLUMINANCE BEFORE EXPOSURE
ILLUMINANCE DURING EXPOSURE
ILLUMINANCE AFTER EXPOSURE
DUMMY WAFER

ILLUMINANCE BEFORE EXPOSING
DUMMY WAFER

ILLUMINANCE DURING EXPOSURE
OF FIRST WAFER

ILLUMINANCE AFTER EXPOSURE
OF FIRST WAFER

ILLUMINANCE BEFORE EXPOSURE
OF FIRST WAFER

ILLUMINANCE
EXPOSURE
OF
DUMMY
WAFER

ILLUMINANCE AFTER EXPOSURE
OF FIRST WAFER

ILLUMINANCE BEFORE
EXPOSURE OF
SECOND WAFER

ILLUMINANCE AFTER
EXPOSURE OF
SECOND WAFER

ILLUMINANCE BEFORE
EXPOSURE OF
THIRD WAFER

NUMBER OF APPLIED PULSES (EXPOSURE TIME)

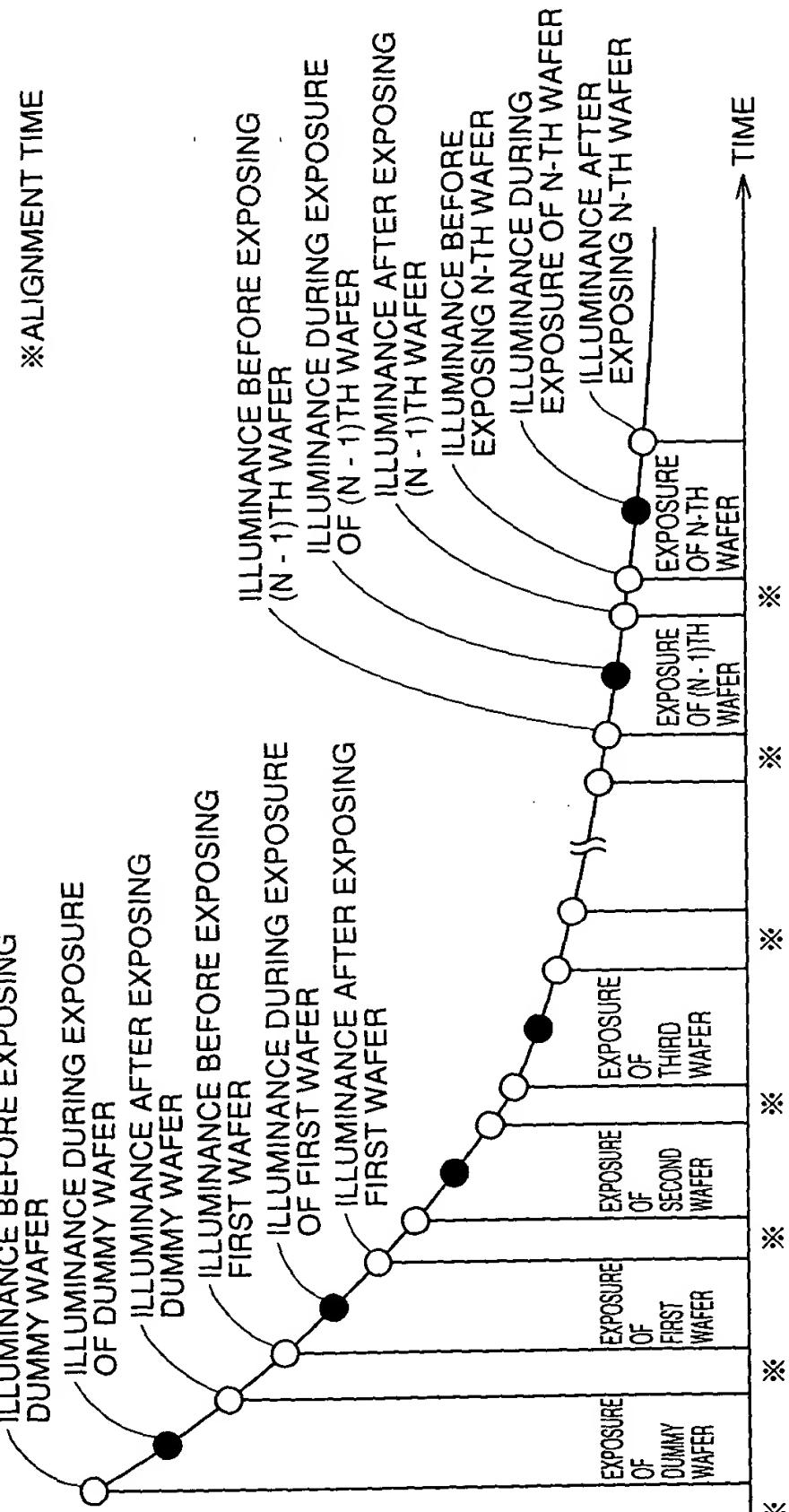


FIG.4

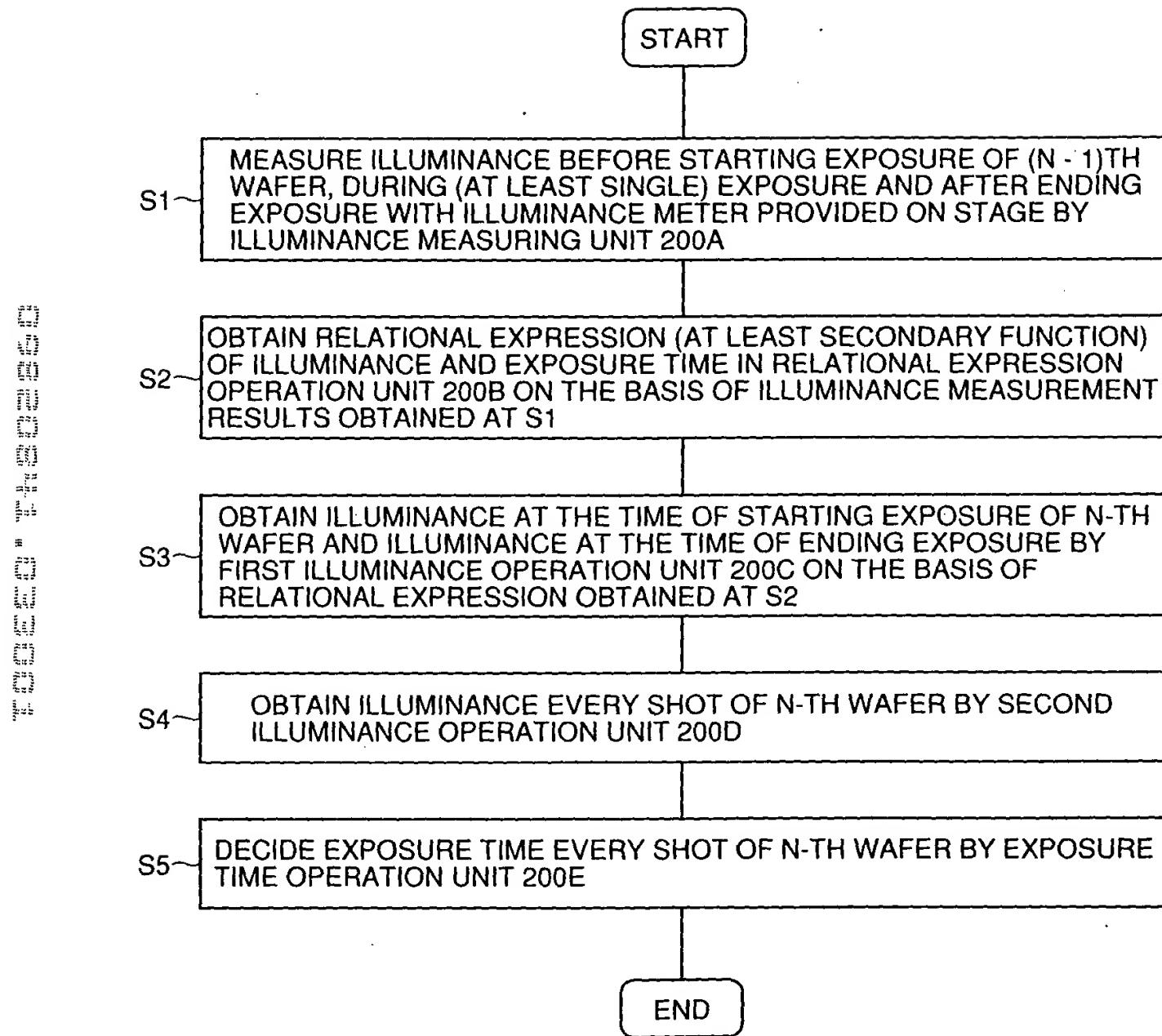


FIG.5

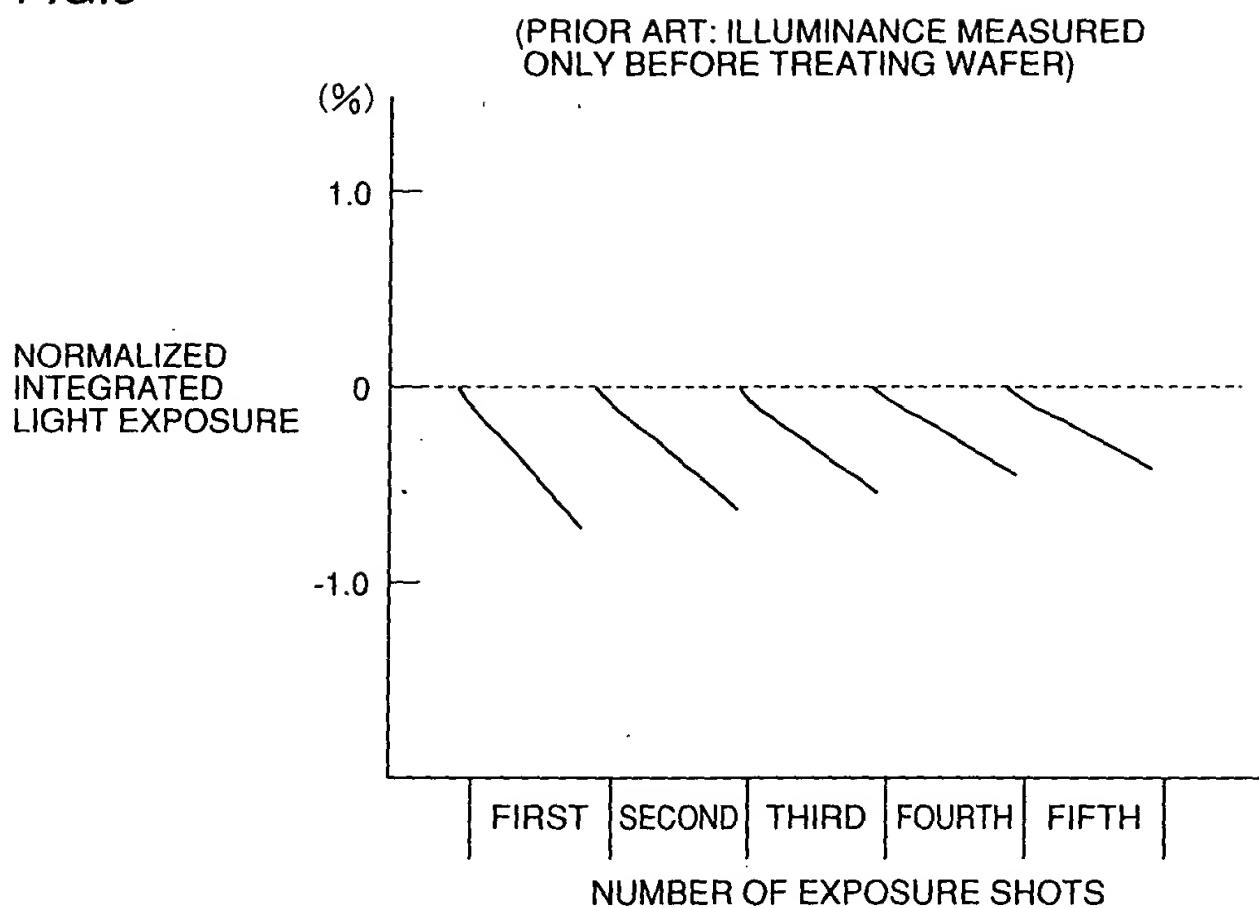


FIG.6

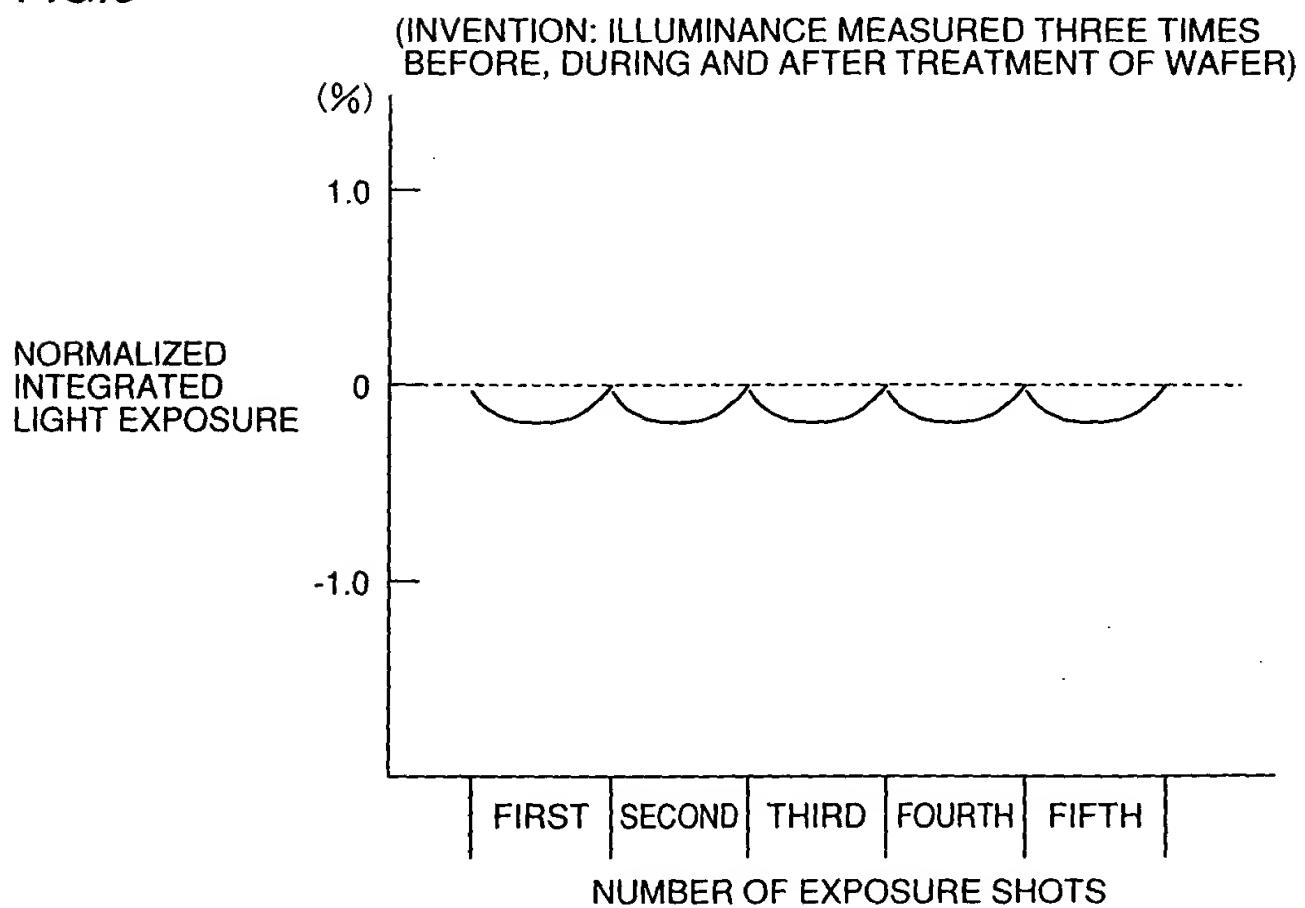


FIG.7

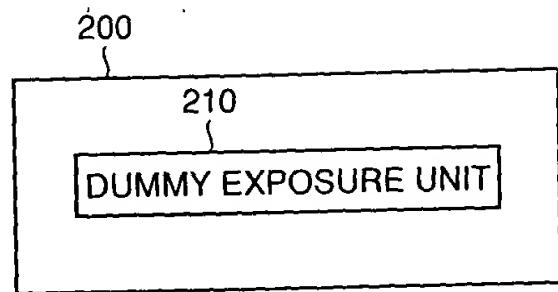


FIG.8 PRIOR ART

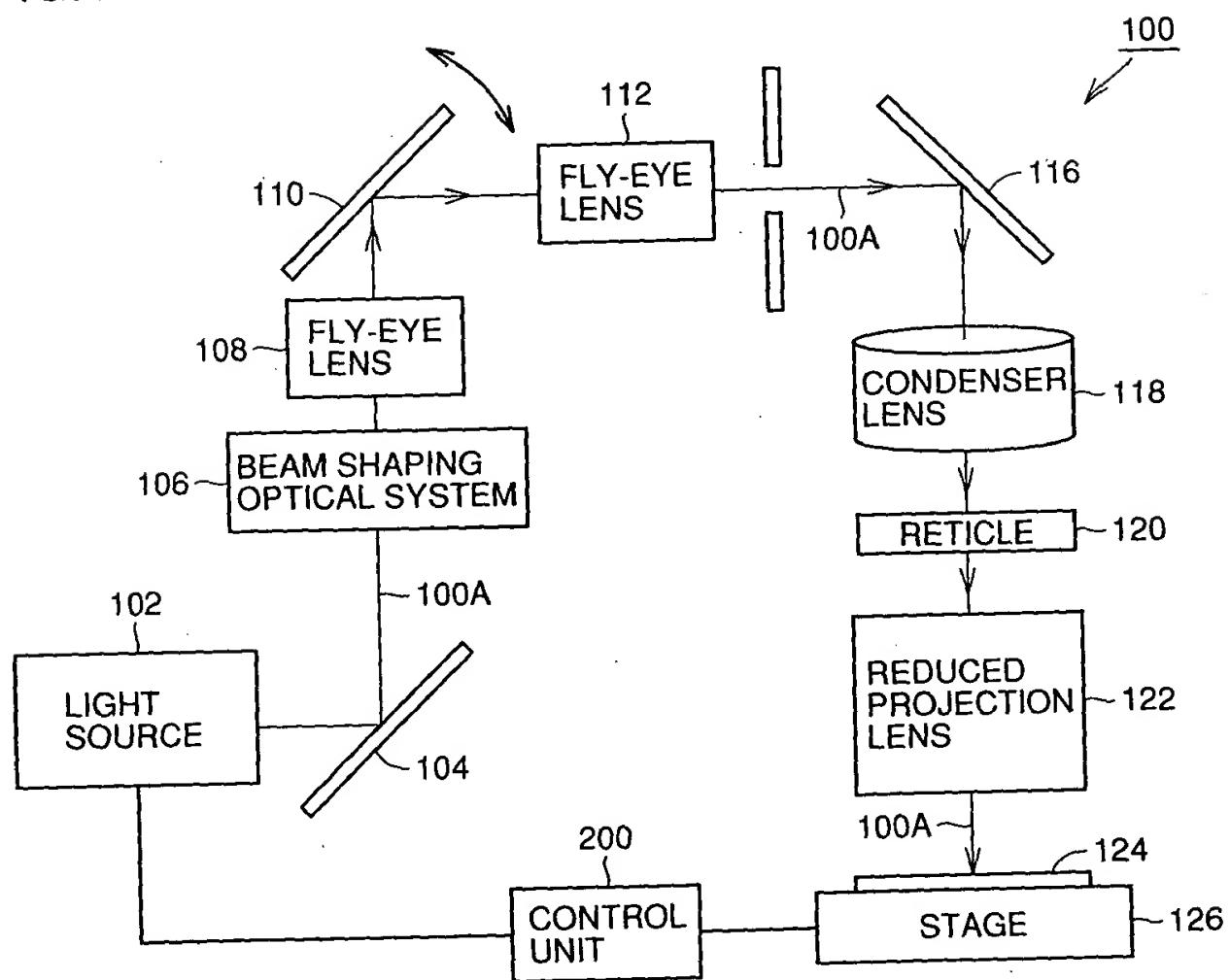


FIG.9 PRIOR ART

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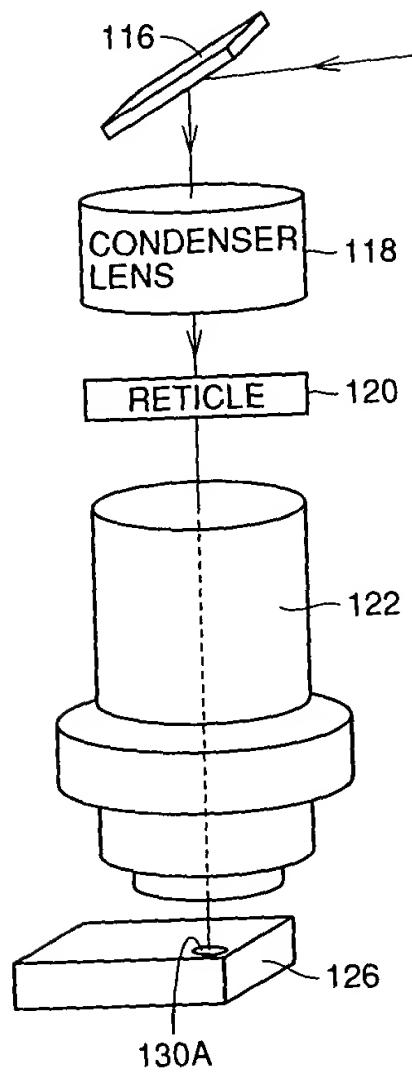


FIG. 10 PRIOR ART

